	L #	Hits	Search Text	DBs	Time Stamp
1	L1	6655	micron.asn.	USPAT; US-PGPUB	2002/02/09 12:39
2	L4	63093	(wet water steam) near15 (oxidation oxidiz$3 oxidis$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 12:41
3	L11	262	1 and 4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 12:41
4	L18	43	11 and (RTP RTA RTO (rapid adj thermal))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:14
5	L25	29	1 and (4 same (gate adj2 (oxide dioxide dielectric insulation insulator insulating)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:25
6	L32	75360	gate adj2 (oxide dioxide dielectric insulation insulator insulating)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:26
7	L39	28959	high adj2 (k dielectric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2002/02/09 13:27
8	L46	6500	(ditantalum tantalum) adj (oxide pentaoxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:27
9	L53	1980	(ditantalum tantalum) adj pentoxide	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:27
10	L60	8200	46 53	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:28
11	L67	542	32 near15 39	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:28
12	L74	495	32 near10 39	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:28
13	L81	220	32 near10 60	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:29
14	L88	655	74 81	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 13:29
15	L95	51	88 and 4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 14:40
16	L102	1	6063698.urpn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 14:40

	L #	Hits	Search Text	DBs	Time Stamp
1	L1	8200	((ditantalum tantalum) adj (oxide pentaoxide)) ((ditantalum tantalum) adj pentoxide)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 16:53
2	L8	542	(gate adj2 (oxide dioxide dielectric insulation insulator insulating)) near15 (high adj2 (k dielectric))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 16:54
3	L15	5920	"Ta.sub.2" adj "O.sub.5"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 16:53
4	L22	12061	1 15	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 16:53
5	L29	393	(gate adj2 (oxide dioxide dielectric insulation insulator insulating)) near15 22	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 18:29
6	L36	71849	((wet water steam ("H.sub.2" adj O) moisture) near15 (anneal$3 oxidation oxidiz$3 oxidis$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 17:35
7	L50	2	43 and (8 29)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 16:57
8	L43	48	36 near25 22	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 16:58
9	L57	39	4495219.URPN.	USPAT	2002/02/09 17:05
10	L58	13	5292673.URPN.	USPAT	2002/02/09 17:09
11	L59	1998	22 same (anneal$3 oxidation oxidiz$3 oxidis$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 17:36
12	L66	132	59 and 29	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 17:36
13	L73	34	66 and ((rapid adj thermal) or RTA or RTP or RTO)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 17:37
14	L80	0	29 and luan.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 18:29
15	L87	3	29 and kwong.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 18:31
16	L94	3	29 and Wu.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/02/09 18:31